AMENDMENTS TO THE CLAIMS:

This following listing of claims replaces all prior listings, and all prior versions, of claims in the application.

Listing Of Claims:

1-73. (Cancelled).

74. (New) A metal-polishing liquid material comprising an ingredient group of an oxidized-metal etchant, a protective film-forming agent and at least one of esters, ethers, polysaccharides, salts of amino acids, polycarboxylic acids, salts of polycarboxylic acids, vinyl polymers, sulfonic acids, sulfonates, and amides.

75. (New) The metal-polishing liquid material according to claim 74, further comprising at least one of an oxidizing agent and water.

76. (New) The metal-polishing liquid material according to claim 74, comprising the ingredient group of the metal-polishing liquid in a divided state of at least two constituent elements not mixed.

77. (New) The metal-polishing liquid material according to claim 74, wherein at least a part of the protective film-forming agent is solid having a mean particle size of at most 100 μm.

78. (New) The metal-polishing liquid material according to claim 74, further comprising abrasive grains.

79. (New) A metal-polishing liquid which comprises an oxidizing agent, an oxidized-metal etchant, a protective film-forming agent, at least one of esters, ethers, polysaccharides, salts of amino acids, polycarboxylic acids, salts of polycarboxylic acids, vinyl polymers, sulfonic acids, sulfonates, and amides, and water.

80. (New) The metal-polishing liquid according to claim 79, wherein at least a part of the protective film-forming agent is solid, having a mean particle size of at most 100 μm.

81. (New) The metal-polishing liquid according to claim 79, further comprising abrasive grains.

82. (New) A method for producing a metal-polishing liquid, comprising a step of diluting the metal-polishing liquid material of claim 74 with a diluent.

83. (New) A method for producing a metal-polishing liquid of claim 79, comprising a step of diluting a metal-polishing liquid material comprising at least one ingredient of the ingredient group of the metal-polishing liquid with an aqueous solution for dilution of at least one ingredient of the ingredient group.

84. (New) A method for producing a metal-polishing liquid of claim 79, which comprises a step of mixing the following in any desired order:

a first constituent element that contains at least one ingredient of the ingredient group of the metal-polishing liquid,

a second constituent element that contains at least one of the other

ingredients of the ingredient group, and

a diluent.

85. (New) The method for producing a metal-polishing liquid according to claim 84, wherein the diluent is water or an aqueous diluent solution.

86. (New) The method for producing a metal-polishing liquid according to claim 84,

wherein

the first constituent element comprises an oxidizing agent, and

the second constituent element comprises

an oxidized-metal etchant,

a protective film-forming agent, and

any one selected from the following (1)-(4):

(1) at least one of esters, ethers, polysaccharides, salts of amino acids, polycarboxylic acids, salts of polycarboxylic acids, vinyl polymers, sulfonic acids, sulfonates, and amides,

(2) a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter,

(3) a good solvent of the solubility of the protective film-forming agent, and

(4) at least one of alcohols, ethers and ketones.

87. (New) The method for producing a metal-polishing liquid according to claim 84, wherein the first constituent element further comprises at least one selected from the following (1)-(5):

(1) the protective film-forming agent and the dissolution promoter,

(2) the protective film-forming agent and at least one of esters, ethers, polysaccharides, salts of amino acids, polycarboxylic acids, salts of polycarboxylic acids, vinyl polymers, sulfonic acids, sulfonates, and amides,

(3) the protective film-forming agent and the solvent in which the solubility of the protective film-forming agent is at least 25 g/liter,

(4) the protect film-forming agent and the good solvent for the protective film-forming agent, and

(5) the protective film-forming agent and at least one of alcohols, ethers and ketones.

88. (New) The method for producing a metal-polishing liquid as claimed in claim 84, wherein in the mixing step, the oxidizing agent and the oxidizing agent-containing mixture are kept at a temperature of at most 40°C.

89. (New) The method for producing a metal-polishing liquid as claimed in claim 84, wherein at least a part of the protective film-forming agent is solid, having a mean particle size of at most 100 μm, and is dissolved or dispersed in the metal-polishing liquid in the mixing step.

90. (New) A polishing method comprising a polishing step of:

applying the metal-polishing liquid of claim 79 to a polishing pad set on a platen, and

polishing the surface of an article to be polished with the polishing pad by moving the polishing pad and the surface of the article relatively to each other while keeping the surface of the article in contact with the polishing pad.

91. (New) The polishing method according to claim 90, further comprising a step of mixing the constituent elements of the metal-polishing liquid to prepare the metal-polishing liquid, prior to the polishing step,

wherein the mixing step is for mixing the following:

a first constituent element that contains at least one ingredient of the ingredient group,

a second constituent element that contains at least one of the other ingredients of the ingredient group, and

a diluent, in any desired order.

92. (New) A method for producing a metal-polishing liquid, comprising a step of diluting the metal-polishing liquid material of claim 82 with a diluent.

93. (New) The method for producing a metal-polishing liquid according to claim 82, wherein the diluent is water or an aqueous diluent solution.

94. (New) The metal-polishing liquid material according to claim 76, wherein each ingredient of said ingredient group is a different ingredient.

95. (New) The metal-polishing liquid material according to claim 75,

wherein the protective film-forming agent, the dissolution promoter, the oxidized-metal etchant, the oxidizing agent and water are different ingredients.

96. (New) The metal-polishing liquid material according to claim 74, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts

of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

97. (New) The metal-polishing liquid according to claim 79,

wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

98. (New) A metal-polishing liquid material comprising an ingredient group of an oxidized-metal etchant, a protective film-forming agent, and a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

99. (New) A metal-polishing liquid material comprising an ingredient group of an oxidized-metal etchant, a protective film-forming agent, and a good solvent for the protective film-forming agent.

100. (New) A metal-polishing liquid material comprising an ingredient group of an oxidized-metal etchant, a protective film-forming agent, and at least one of alcohols, ethers and ketones.

101. (New) A metal-polishing liquid material comprising an ingredient group of an oxidized-metal etchant, a protective film-forming agent, and a dissolution promoter for the protective film-forming agent, wherein

a polishing liquid is prepared by diluting the metal-polishing liquid material with at least 10-fold dilution factor of the metal-polishing liquid material.

102. (New) The metal-polishing liquid material according to claim 98, further comprising at least one of an oxidizing agent and water.

103. (New) The metal-polishing liquid material according to claim 99, further comprising at least one of an oxidizing agent and water.

104. (New) The metal-polishing liquid material according to claim 100, further comprising at least one of an oxidizing agent and water.

105. (New) The metal-polishing liquid material according to claim 101, further comprising at least one of an oxidizing agent and water.

106. (New) The metal-polishing liquid material according to claim 98, comprising the ingredient group of the metal-polishing liquid material in a divided state at least into two constituent elements not mixed.

107. (New) The metal-polishing liquid material according to claim 99, comprising the ingredient group of the metal-polishing liquid material in a divided state of at least two constituent elements not mixed.

108. (New) The metal-polishing liquid material according to claim 100, comprising the ingredient group of the metal-polishing liquid material in a divided state of at least two constituent elements not mixed.

109. (New) The metal-polishing liquid material according to claim 101, comprising the ingredient group of the metal-polishing liquid material in a divided

state of at least two constituent elements not mixed.

110. (New) The metal-polishing liquid material according to claim 101, wherein the dissolution promoter is a surfactant.

111. (New) The metal-polishing liquid material according to claim 101, wherein the surfactant is at least one of esters, ethers, polysaccharides, salts of amino acids, polycarboxylic acids, salts of polycarboxylic acids, vinyl polymers, sulfonic acids, sulfonates, and amides.

112. (New) The metal-polishing liquid material according to claim 99, wherein the dissolution promoter is a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

113. (New) The metal-polishing liquid material according to claim 100, wherein the dissolution promoter is a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

114. (New) The metal-polishing liquid material according to claim 101, wherein the dissolution promoter is a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

115. (New) The metal-polishing liquid material according to claim 98, wherein the solvent is a good solvent for the protective film-forming agent.

116. (New) The metal-polishing liquid material according to claim 100, wherein the solvent is a good solvent for the protective film-forming agent.

117. (New) The metal-polishing liquid material according to claim 101, wherein the solvent is a good solvent for the protective film-forming agent.

118. (New) The metal-polishing liquid material according to claim 98, wherein the solvent is at least one of alcohols, ethers and ketones.

119. (New) The metal-polishing liquid material according to claim 99, wherein the solvent is at least one of alcohols, ethers and ketones.

120. (New) The metal-polishing liquid material according to claim 101, wherein the solvent is at least one of alcohols, ethers and ketones.

121. (New) The metal-polishing liquid material according to claim 98, wherein the amount of the solvent is smaller than 50 g relative to 100 g of a total amount of the material.

122. (New) The metal-polishing liquid material according to claim 99, wherein the amount of the solvent is smaller than 50 g relative to 100 g of a total amount of the material.

123. (New) The metal-polishing liquid material according to claim 100, wherein the amount of the solvent is smaller than 50 g relative to 100 g of a total amount of the material.

124. (New) The metal-polishing liquid material according to claim 98, wherein at least a part of the protective film-forming agent is solid having a mean particle size of at most 100 μm.

125. (New) The metal-polishing liquid material according to claim 99, wherein at least a part of the protective film-forming agent is solid having a mean particle size of at most 100 μm.

126. (New) The metal-polishing liquid material according to claim 100, wherein at least a part of the protective film-forming agent is solid having a mean particle size of at most 100 μm.

127. (New) The metal-polishing liquid material according to claim 101, wherein at least a part of the protective film-forming agent is solid having a mean particle size of at most 100 μm.

128. (New) The metal-polishing liquid material according to claim 98, further comprising abrasive grains.

129. (New) The metal-polishing liquid material according to claim 99, further comprising abrasive grains.

130. (New) The metal-polishing liquid material according to claim 100, further comprising abrasive grains.

131. (New) The metal-polishing liquid material according to claim 101, further comprising abrasive grains.

132. (New) A metal-polishing liquid comprising an ingredient group of an oxidizing agent, an oxidized-metal etchant, a protective film-forming agent, a solvent and water,

wherein the solubility of the protective film-forming agent in the solvent is at least 25 g/liter.

133. (New) A metal-polishing liquid comprising an ingredient group of an oxidizing agent, an oxidized-metal etchant, a protective film-forming agent, a good solvent for the protective film-forming agent and water.

134. (New) A metal-polishing liquid comprising an ingredient group of an oxidizing agent, an oxidized-metal etchant, a protective film-forming agent, at least one of alcohols, ethers and ketones, and water.

135. (New) The metal-polishing liquid according to claim 133, wherein the dissolution promoter is a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

136. (New) The metal-polishing liquid according to claim 134, wherein the dissolution promoter is a solvent in which the solubility of the protective film-forming agent is at least 25 g/liter.

137. (New) The metal-polishing liquid according to claim 132, wherein at

least a part of the protective film-forming agent is solid, having a mean particle size of at most 100 μm.

138. (New) The metal-polishing liquid according to claim 133, wherein at least a part of the protective film-forming agent is solid, having a mean particle size of at most 100 μm.

139. (New) The metal-polishing liquid according to claim 134, wherein at least a part of the protective film-forming agent is solid, having a mean particle size of at most 100 μm.

140. (New) The metal-polishing liquid according to claim 132, further comprising abrasive grains.

141. (New) The metal-polishing liquid according to claim 133, further comprising abrasive grains.

142. (New) The metal-polishing liquid according to claim 134, further comprising abrasive grains.

143. (New) A method for producing a metal-polishing liquid of claim 132, comprising a step of diluting a metal-polishing liquid material comprising at least one ingredient of the ingredient group with an aqueous solution for dilution of at least one ingredient of the ingredient group.

144. (New) A method for producing a metal-polishing liquid of claim 133,

comprising a step of diluting a metal-polishing liquid material comprising at least one ingredient of the ingredient group with an aqueous solution for dilution of at least one ingredient of the ingredient group.

145. (New) A method for producing a metal-polishing liquid of claim 134, comprising a step of diluting a metal-polishing liquid material comprising at least one ingredient of the ingredient group with an aqueous solution for dilution of at least one ingredient of the ingredient group.

146. (New) A method for producing a metal-polishing liquid of claim 132, which comprises a step of mixing the following in any desired order:

a first constituent element that contains at least one ingredient of the ingredient group of the metal-polishing liquid,

a second constituent element that contains at least one of the other ingredients of the ingredient group, and

a diluent.

147. (New) A method for producing a metal-polishing liquid of claim 133, which comprises a step of mixing the following in any desired order:

a first constituent element that contains at least one ingredient of the ingredient group of the metal-polishing liquid,

a second constituent element that contains at least one of the other ingredients of the ingredient group, and

a diluent.

148. (New) A method for producing a metal-polishing liquid of claim 134,

which comprises a step of mixing the following in any desired order:

a first constituent element that contains at least one ingredient of the ingredient group,

a second constituent element that contains at least one of the other ingredients of the ingredient group, and

a diluent.

149. (New) A polishing method comprising a polishing step of;

applying the metal-polishing liquid of claim 132 to a polishing pad set on a platen, and

polishing the surface of an article to be polished with the polishing pad by moving the polishing pad and the surface of the article relatively to each other while keeping the surface of the article in contact with the polishing pad.

150. (New) A polishing method comprising a polishing step of;

applying the metal-polishing liquid of claim 133 to a polishing pad set on a platen, and

polishing the surface of an article to be polished with the polishing pad by moving the polishing pad and the surface of the article relatively to each other while keeping the surface of the article in contact with the polishing pad.

151. (New) A polishing method comprising a polishing step of;

applying the metal-polishing liquid of claim 134 to a polishing pad set on a platen, and

polishing the surface of an article to be polished with the polishing pad by moving the polishing pad and the surface of the article relatively to each other while

keeping the surface of the article in contact with the polishing pad.

152. (New) The metal-polishing liquid material according to claim 98, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

153. (New) The metal-polishing liquid material according to claim 99, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

154. (New) The metal-polishing liquid material according to claim 100, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

155. (New) The metal-polishing liquid material according to claim 101, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

156. (New) The metal-polishing liquid material according to claim 132, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

157. (New) The metal-polishing liquid material according to claim 133, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.

158. (New) The metal-polishing liquid material according to claim 134, wherein the protective film-forming agent is at least one selected from the group consisting of ammonia, amines, amino acids, imines, azoles, mercaptans, polysaccharides, salts of amino acids, polycarboxylic acids and their salts, and vinyl polymers.